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Color Code:

Red – Plasma Etching
Blue – Advanced Devices

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US Patent Nr.	Title	Assignee	Filed	Date of Patent
6,573,165	Method of providing polysilicon spacer for implantation	Texas Instruments Incorporated	6/28/02	6/3/03
6,573,167	Using a carbon film as an etch hardmask for hard-to-etch materials	Texas Instruments Incorporated	8/2/01	6/3/03
6,573,190	Dry etching device and dry etching method	Hitachi, Ltd.	5/18/01	6/3/03
6,573,563	SOI semiconductor integrated circuit for eliminating floating body effects in SOI MOSFETs	Samsung Electronics Co., Ltd.	6/1/01	6/3/03
6,577,915	Applications of a semi-empirical, physically based, profile simulator	LAM Research Corporation	6/30/00	6/10/03
6,579,770	Sidewall process and method of implantation for improved CMOS with benefit of low CGD, improved doping profiles, and insensitivity to chemical processing	Texas Instruments Incorporated	7/5/01	6/17/03

6,579,775	Semiconductor device having a metal gate with a work function compatible with a semiconductor device	Agere Systems Inc.	10/24/03	6/17/03
6,579,796	Method of etching platinum using a silicon carbide mask	Applied Materials Inc.	12/10/01	6/17/03
6,579,806	Method of etching tungsten or tungsten nitride in semiconductor structures	Applied Materials Inc.	5/7/02	6/17/03
6,579,809	In-situ gate etch process for fabrication of a narrow gate transistor structure with a high-k gate dielectric	Advanced Micro Devices, Inc.	5/16/02	6/17/03
6,580,132	Damascene double-gate FET	International Business Machines Corporation	4/10/02	6/17/03
6,580,149	Double LDD devices for improved DRAM refresh	Micron Technology, Inc.	1/17/02	6/17/03
6,582,617	Plasma etching using polycarbonate mask and low-pressure high density plasma	Candescent Technologies Corporation	4/29/99	6/24/03
6,582,618	Method of determining etch endpoint using principal components analysis of optical emission spectra	Advanced Micro Devices, Inc.	1/26/00	6/24/03
6,582,891	Process for reducing edge roughness in patterned photoresist	Axcelis Technologies, Inc.	11/14/00	6/24/03
6,582,988	Method for forming micro lens structures	Taiwan Semiconductor Manufacturing Company	7/12/01	6/24/03

6,583,008	Nonvolatile semiconductor memory device and manufacturing method thereof	Samsung Electronics Co.	9/22/02	6/24/03
6,583,012	Semiconductor devices utilizing differently composed metal-based in-laid gate electrodes	Advanced Micro Devices, Inc.	2/13/01	6/24/03
6,583,016	Doped spacer liner for improved transistor performance	Advanced Micro Devices, Inc.	3/26/02	6/24/03
6,583,055	Method of forming stepped contact trench for semiconductor devices	Powerchip Semiconductor	1/25/02	6/24/03
6,583,065	Sidewall polymer forming gas additives for etching processes	Applied Materials Inc.	8/3/99	6/24/03